	Application No.	Applicant(s)
Notice of Allowability	10/620,129	HAUER ET AL.
	Examiner	Art Unit
	THUY V. TRAN	2821
The MAILING DATE of this communication apperature All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this ap or other appropriate communicatio GHTS. This application is subject t	pplication. If not included
1. This communication is responsive to 7/15/2003 & Interview		
2. The allowed claim(s) is/are <u>1-8</u> .		
3. The drawings filed on are accepted by the Examiner		
 4. ☐ Acknowledgment is made of a claim for foreign priority un a) ☐ All b) ☐ Some* c) ☐ None of the: 	der 35 U.S.C. § 119(a)-(d) or (f).	
 Certified copies of the priority documents have 	and the second s	
2. Certified copies of the priority documents have		
Copies of the certified copies of the priority doc	uments have been received in this	national stage application from the
International Bureau (PCT Rule 17.2(a)).		
* Certified copies not received:		
noted below. Failure to timely comply will result in ABANDONMI THIS THREE-MONTH PERIOD IS NOT EXTENDABLE. 5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which gives the complex of the co	tted. Note the attached EXAMINER s reason(s) why the oath or declara	'S AMENDMENT or NOTICE OF tion is deficient.
(a) ☐ including changes required by the Notice of Draftsperso		948) attached
1) hereto or 2) to Paper No./Mail Date		
(b) including changes required by the attached Examiner's Paper No./Mail Date 05052004.	Amendment / Comment or in the C	Office action of
Identifying indicia such as the application number (see 37 CFR 1.8 each sheet. Replacement sheet(s) should be labeled as such in the	34(c)) should be written on the drawing the second in the drawing to 37 CFR 1.121(c)	ngs in the front (not the back) of d).
 DEPOSIT OF and/or INFORMATION about the depos attached Examiner's comment regarding REQUIREMENT F 	it of BIOLOGICAL MATERIAL r OR THE DEPOSIT OF BIOLOGIC	nust be submitted. Note the AL MATERIAL.
Attachment(s)	•	
1. Notice of References Cited (PTO-892)	_	atent Application (PTO-152)
2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)	6. ⊠ Interview Summary Paper No./Mail Dat	
 Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No./Mail Date), 7. Examiner's Amenda	
1. ☐ Examiner's Comment Regarding Requirement for Deposit	8. 🛛 Examiner's Stateme	nt of Reasons for Allowance
of Biological Material	9. ⊠ Other <u>See Continua</u>	tion Sheet.
		THUY V. TRAN Examiner Art Unit: 2821

U.S. Patent and Trademark Office PTOL-37 (Rev. 1-04)

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DETAILED ACTION

This is a response to the Applicants' filing on July 15th, 2003 and the interview held on May 5th, 2004. In virtue of this filing, claims 1-8 are currently presented in the instant application.

Examiner's Amendment

1. An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Mr. Benjamin Hudson, Jr. on May 5th, 2004. The Examiner's amendment includes:

• Amendment to the title:

Change the original title to --AN IMPROVED RF POWER CONTROL DEVICE FOR RF PLASMA APPLICATIONS--;

• Amendment to the Abstract:

Line 1, change "method" to --device--;

Line 11, change "Plasma" to --plasma--; and

Line 12, insert --device and-- between "control" and "methods";

• Amendment to the claims:

Claim 1, line 11, change "are" to --is--;

Claim 1, line 18, change "deliver" to --delivered--;

Claim 5, line 2, change "a" (first occurrence) to --an--;

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Claim 5, line 11, change "are" to --is--;

Claim 5, line 12, change "forward and reflected signal mixers" to --a first mixer--;

Claim 5, line 19, insert -- a-- between "to" and "second";

Claim 5, line 20, insert --to-- between "connected" and "the"; and replace "forward

and reflected signal mixers" with --first mixer--;

Claim 5, line 26, change "deliver" to --delivered--; and

Claim 6, line 3, change "forward and reflected signal mixers" to --first mixer--;

• Amendment to the specification:

Page 3, line 16, change "10" to --10'--;

Page 3, line 22, change "20" to --20'--;

Page 3, line 23, change "22" to --22'--; change "24" to --24'--; and change "26" to --26'--;

Page 3, line 24, change "30" to --30'--; and change "32" to --32'--;

Page 4, line 16, change "30, 32" to --30', 32'--;

<u>Amendment to the drawings:</u>

In FIGURE 2:

Change "10" to --10'--;

Change "18" to --output to matching network and plasma--;

Change "20" to --20'--;

Change "22" to --22'--;

Change "24" to --24'--:

Change "26" to --26'--;

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Change "30" to --30'--;

Change "32" to --32'--;

In FIGURE 3:

Change "output" to --output to matching network and plasma--; and

In FIGURE 4:

Change "output" to --output to matching network and plasma--;

Insert "REFL" on the opposite side of "FWD".

Allowable Subject Matter

2. Claims 1-8 are allowed.

Reasons for Allowance

3. The following is an examiner's statement of reasons for allowance:

Prior art fails to disclose or fairly suggest:

A VHF generator for delivering RF power to a plasma comprising (1) each of the sampled forward and reflected signals is connected to mixers for mixing with an intermediate frequency of an oscillator, (2) the mixed forward and reflected signals are passed through low-pass filters, (3) the filtered forward and reflected signals are connected to amplifiers and detectors, and (4) the detected forward and reflected signals are fed back to a power control circuit wherein the power delivered to the plasma is monitored without interference from spurious frequency signals generated by the plasma, in combination with the remaining claimed limitations as called for in independent claim 1 (claims 2-4 are allowed since they are dependent on claim 1); and

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A VHF generator for delivering RF power to a plasma comprising (1) a first oscillator connected to a second mixer for mixing a sampled output of the variable RF signal generator with a first intermediate frequency, (2) the output of the second mixer is connected to a first band pass filter and then connected to a third mixer for mixing with a second intermediate frequency of a second oscillator, (3) the output of the third mixer is connected to a second band-pass filter and connected to the first mixer, (4) the mixed forward and reflected signals are passed through low pass filters, (5) the filtered forward and reflected signals are connected to amplifiers and detectors, and (6) the detected forward and reflected signals are fed back to a power control circuit wherein the power delivered to the plasma is monitored without interference from spurious frequency signals generated by the plasma, in combination with the remaining claimed limitations as called for in independent claim 5 (claims 6-8 are allowed since they are dependent on claim 5).

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Citation of relevant prior art

4. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Prior art Reyzelman et al. (U.S. Patent No. 6,703,080) discloses a method and apparatus for VHF plasma.

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Prior art Chen et al. (U.S. Patent No. 6,472,822) discloses a pulsed RF power delivery for plasma processing.

Prior art Wilbur (U.S. Patent No. 6,020,794) discloses an RF plasma system.

Prior art Turner et al. (U.S. Patent No. 5,939,886) discloses a plasma monitoring and control method and system.

Prior art Barnes et al. (U.S. Patent No. 5,892,198) discloses a method and apparatus for controlling RF plasma processor.

Prior art Benjmin et al. (U.S. Patent No. 5,708,250) discloses an RF plasma processor.

Prior art Mavretic et al. (U.S. Patent No. 5,654,679) discloses an apparatus for matching a variable load impedance with an RF power generator impedance.

Inquiry

Any inquiry concerning this communication or earlier communications from the examiner should be directed to THUY V. TRAN whose telephone number is (571) 272-1828. The examiner can normally be reached on M-F (8:30 AM-6:00 PM).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, DON K. WONG can be reached on (571) 272-1834. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

THUY V. TRAN Examiner Art Unit 2821

T.T. 05/05/2004

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